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# The micro-RWELL technology:

from the R&D to the technology transfer towards Industry

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DDG - LNF-INFN CERN-CH, INFN – Bologna, INFN – Ferrara, ELTOS SpA

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G. Bencivenni et al., The micro-Resistive WELL detector: a compact spark-protected single amplification-stage MPGD, 2015 JINST 10 P02008



The  $\mu$ -RWELL is a resistive MPGD composed of two elements:

- Cathode
- μ-RWELL\_PCB:

The µ-RWELL

- a WELL patterned kapton foil (w/Cu-layer on top) acting as amplification stage
- a resisitive DLC layer<sup>(\*)</sup> w/ $\rho$ ~10÷100 M $\Omega$ / $\Box$
- a standard readout PCB with pad/strip segmentation

<sup>(\*)</sup> DLC foils are currently provided by the Japan Company – BeSputter



The **"WELL"** acts as a **multiplication channel** for the ionization produced in the drift gas gap.

The resistive stage ensures the spark amplitude quenching.

**Drawback:** capability to stand high particle fluxes reduced, but **largely recovered** with appropriate **grounding schemes** of the **resistive layer** 

## The HR layout



The PEP layout (Patterning – Etching – Plating) is the state of art of the high rate layout of the  $\mu$ -RWELL

- Single DLC layer
- Grounding line from top by kapton etching and plating (pitch 1/cm)
- No alignment problems
- High rate capability
- Scalable to large size (up to 1.2x0.5 m for the upgrade of CLAS12)





## LHCb upgrade II (Run5 – Run6)

#### LHCb muon apparatus Run5 – Run6 option detector requirements

- Rate up to **1 MHz/cm<sup>2</sup>** on detector single gap
- Rate up to 700 kHz per electronic channel
- Efficiency quadrigap >=99% within a BX (25 ns)
- Stability up to **1C/cm<sup>2</sup>** accumulated charge in 10 y of operation (M2R1, G=4000)

### Detector size & quantity (4 gaps/chamber - redundancy)

- R1÷R2: 576 detectors, size 30x25 to 74x31 cm<sup>2</sup>, 90 m<sup>2</sup> detector (130 m<sup>2</sup> DLC)
- R3: 768 detectors, siz 120x25 to 149x31 cm<sup>2</sup>, 290m<sup>2</sup> det.
- R4 : 3072 detectors, size 120x25 to 149x31 cm<sup>2</sup>, 1164 m<sup>2</sup> det.







## $\mu\text{-}RWELL$ in HEP/NP & beyond

- **1.** FCC-ee: pre-shower & muon systems of the IDEA apparatus  $\rightarrow$  large area (~4000m<sup>2</sup>) to be instrumented w/tracking detectors
- **2.** CLAS12 @ JLAB: upgrade of the muon spectrometer  $\rightarrow$  large area (1.2x0.5m<sup>2</sup>) low-mass tracking detectors

2, 3

- 3. X17 @ n\_TOF EAR2: small -TPC for the detection of the X17 boson  $\rightarrow$  low mass tracking detectors
- **4. EURIZON**: R&D on IT based on cylindrical micro-RWELL for a SCTF  $\rightarrow$  *low mass tracking detectors*
- **5.** UKRI: thermal neutron detection with pressurized <sup>3</sup>He-CF4 gas mixtures  $\rightarrow$  neutron tracking device
- 6. TACTIC @ YORK Univ.: radial TPC for nuclear reactions w/astrophysical significance  $\rightarrow$  low mass flexible tracking detectors
- 7. URANIA-V: funded by CSN5 for neutron detection  $\rightarrow$  large pad (10x10cm<sup>2</sup>) tile detectors for radiation portal monitor
- **8.** Muon collider: HCAL R&D  $\rightarrow$  pad tile detectors,







## **Technology transfer (I)**



## Technology transfer (II)

Step 0 - Detector PCB design @ LNF

- Step 1 CERN\_INFN DLC sputtering machine @ CERN\_(+INFN)
  - delivery foreseen by the end of Oct. 2022
  - INFN crew tbd & trained
- Step 2- Producing readout PCB by ELTOS
  - pad/strip readout
- Step 3 DLC patterning by ELTOS
  - photo-resist  $\oplus$  patterning with BRUSHING-machine
- Step 4 DLC foil gluing on PCB by **ELTOS** 
  - double 106-prepreg  ${\sim}2x50\mu m$  thick
  - PCB planarizing w/ screen printed epoxy  $\oplus$  single 106-prepreg
- Step 5 Top copper patterning by CERN (in future by ELTOS)
  - Holes image and HV connections by Cu etching
- Step 6 Amplification stage patterning by CERN
  - PI etching  $\oplus$  plating  $\oplus$  ampl-holes

Step 7 – Electrical cleaning and detector closing @  $\ensuremath{\textbf{CERN}}$ 







## **CID: the CERN-INFN DLC machine**

... some infos extract from the machine Contract

- The machine shall be able to coat flexible substrates with areas of up to 1.7 m × 0.6 m
- The machine shall be able to coat **rigid substrates** with areas of up to **0.2 m** × **0.6 m**
- Five cooled target holders, arranged as two pairs face to face and one on the front, equipped with five shutters
- The machine shall be able to **sputter or co-sputter different materials,** in order to create a coating layer by layer or an adjustable gradient in the coating
- The Contractor shall provide **training for the CERN-INFN personnel** concerned, at the CERN site. The aim of the training course is to ensure that personnel is able to:
  - Program and pilot the process with the machine
  - Conduct a failure analysis on the machine





### Summary

- The driving force behind the development of the resistive MPGDs is the spark quenching and charge spreading technique to optimize readout plane
- DLC coatings opened the way to develop new detector structures.
  The μ-RWELL is one of the examples of emerging MPGD technologies that are evolving and profiting from the on-going developments on DLC
- The challenge for the next years is the TT of resistive-MPGD technology to PCB industry
- Key-point of the industrialization has been the acquisition of a DLC magnetron sputtering machine co-funded by CERN and INFN that will enter in operation in 2023
- Other items under study:
  - **2D strip readout**  $\rightarrow$  2D w/top readout, 2D with capacitive sharing
  - Global irradiation (GIF, X-ray tube, Calliope source)
  - Eco-gas fast mixtures (essentially for LHCb)
  - APV25 w/SRS is a user-friendly electronics for testing MPGD. VMM3 integration w/SRS in progress (RD51). The Bari group (*G. De Robertis, F. laciulli, F. Loddo*) is developing a new ASIC (FATIC) that will be tested for the μ-RWELL (LHCb). Under study an update version of TIGER (developed for BESIII CGEM by Torino group)
- Sinergy among different groups working on different resistive MPGD technologies (μ-RWELL/MM) for common tooling (DLC machine) should be promoted for the development of high-performance hybrid structures

L3=85,65µm

**Spare Slides** 

L1=83,76µm

L2=88,87µm



## The low-rate layout





### Single Resistive Layer (SRL)

- **2-D current evacuation** scheme based on a single resistive layer
- grounding around the perimeter of the active area
- limited rate capability <100 kHz/cm<sup>2</sup>

## **High-rate layouts**



### The Silver Grid

- simplified HR scheme based on SRL
- **2-D evacuation scheme** by means a conductive grid realized on the DLC layer
- grid lines can be screen-printed or etched by photo-lithography
- pitch of the grid lines of the order of 1/cm

### **Double Resistive Layer**

- 3-D current evacuation scheme
- two stacked resistive layers connected through a matrix of conductive vias
- Resistive stage grounding through a further matrix of vias to the underlying readout electrodes
- pitch of the vias with a density less than 1/cm<sup>2</sup>



## High-rate layouts: performance w/X-rays



## High-rate layouts performance w/m.i.p.



The micro-RWELL layouts for high particle rate, G. Bencivenni et al., 2019\_JINST\_14\_P05014